

<b>Notice of References Cited</b>	Application/Control No. 09/912,398	Applicant(s)/Patent Under Reexamination INANAMI ET AL.	
	Examiner Thomas H. Stevens	Art Unit 2123	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,090,528	07-2000	Gordon et al.	430/296
	B	US-6,363,488	03-2002	Ginter et al.	713/201
	C	US-6,578,174	06-2003	Zizzo, Claudio	716/1
	D	US-5,663,891	09-1997	Bamji et al.	716/2
	E	US-5,971,585	10-1999	Dangat et al.	700/102
	F	US-5,539,652	07-1996	Tegethoff, Mauro V.	703/14
	G	US-5,512,765	04-1996	Gaverick, Timothy L.	257/202
	H	US-5,629,845	05-1997	Liniger, Werner	700/67
	I	US-6,560,768	05-2003	Inanami et al.	716/21
	J	US-5,341,302	08-1994	Connors et al.	700/102
	K	US-4,310,743	01-1982	Seliger, Robert L.	219/121.12
	L	US-6,801,881	10-2004	Shah, Sunil C.	703/2
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Pfeiffer-H.C., "Electron Beam Lithography: A Key to VLSI" IEEE N.Y., N.Y., pg. 186 CPP Conference Paper.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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